

PATENT APPLICATION

**RESPONSE UNDER 37 CFR §1.116
EXPEDITED PROCEDURE
TECHNOLOGY CENTER ART UNIT 1722**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Tsuyoshi NISHIZAWA

Group Art Unit: 1722

Application No.: 10/561,957

Examiner: S. MALEKZADEH

Filed: December 22, 2005

Docket No.: 126273

For: METHOD FOR PRODUCING SILICON EPITAXIAL WAFER AND SILICON
EPITAXIAL WAFER

AMENDMENT AFTER FINAL REJECTION UNDER 37 CFR §1.116

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In reply to the September 27, 2007 Office Action, the period for reply being extended
by the attached Petition for Extension of Time, please consider the following:

Amendments to the Claims as reflected in the listing of claims; and

Remarks.